



# Joint MSIG, MEMS Substrate and Material Characterization TFs

SEMICON West 2018 Standards Meetings

Thursday, July 12, 2018

Marriott Marquis, San Francisco, CA

13:00–15:00

## AGENDA

	<b>Time</b>
<b>1 Welcome/Call to Order</b>	<b>13:00</b>
1.1 Introductions	
1.2 Meeting Objectives	
<b>2 Presentations</b>	<b>13:10</b>
2.1 Mark Tondra (Diagnostic Biosensors) – Microfluidics	
2.2 Paul Trio (SEMI) – Semiconductor Components, Instruments, and Subsystems (SCIS) Technology Community	
<b>3 Existing Documents Under Development</b>	<b>13:30</b>
3.1 6007: New Standard, Specification for a Test Pattern for Deep Reactive Ion Etching (DRIE) Process Characterization	
3.2 6018: New Standard, Specification for Silicon Substrates used in fabrication of MEMS Devices	
3.3 Standard Parameter Definitions Document V2.0	
<b>4 Topics to Explore</b>	<b>14:00</b>
<b>5 Next Steps</b>	<b>14:45</b>
<b>6 Action Item Review</b>	<b>14:50</b>
<b>7 Next Meeting and Adjournment</b>	<b>14:55</b>

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